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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/664,875	09/22/2003	Naoteru Matsubara	65933-044	4231	
7590 09/13/2007 McDERMOTT, WILL & EMERY 600 13th Street, N.W. Washington, DC 20005-3096			EXAMINER		
			IM, JUNGHWA M		
washington, DC 20003-3090			ART UNIT	PAPER NUMBER	
			2811		
			MAIL DATE	DELIVERY MODE	
			09/13/2007	PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

	Application No.	Applicant(s)			
Office Action Summer	10/664,875	MATSUBARA ET AL.			
Office Action Summary	Examiner	Art Unit			
The MAN INC DAME	Junghwa M. Im	2811			
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the c	orrespondence address			
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. Extensions of time may be available under the provisions of 37 CFR 1.1: after SIX (6) MONTHS from the mailing date of this communication. If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period of Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be time y within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from Cause the application to become ARANDONE	s will be considered timely. the mailing date of this communication.			
Status					
1) Responsive to communication(s) filed on 18 Ju	ıne 2007.				
	action is non-final.	·			
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	3 O.G. 213.			
Disposition of Claims					
 4) Claim(s) 1-5 and 18-22 is/are pending in the appear 4a) Of the above claim(s) is/are withdraw 5) Claim(s) is/are allowed. 6) Claim(s) 1-5 and 18-22 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or 	wn from consideration.	,			
Application Papers					
9) The specification is objected to by the Examine					
10) ☐ The drawing(s) filed on is/are: a) ☐ acce					
Applicant may not request that any objection to the					
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Ex	ion is required if the drawing(s) is obj	ected to. See 37 CFR 1.121(d).			
	ammer. Note the attached Office	Action or form PTO-152.			
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Application ity documents have been receive u (PCT Rule 17.2(a)).	on No d in this National Stage			
Attachment(s)					
Notice of References Cited (PTO-892)	4) Interview Summary	(PTO-413)			
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	Paper No(s)/Mail Da				

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DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-5 and 18-22 are rejected under 35 U.S.C. 103(a) as being unpatentable over Gates et al. (US Pat. 6,603,204), hereinafter Gates in view of Watanabe et al. (US Pat. Pub. 2002/0008323), hereinafter Watanabe.

Regarding claims 1 and 18, Fig. 8 of Gates shows a semiconductor device comprising: a semiconductor substrate [50];

a multilayered film including a first dielectric film [54'], an etching stopper [56'] and a second dielectric film [58'] stacked on said semiconductor substrate in this order; and

a via plug [a narrow portion of the metal layer 74 in the layer 54'] and a metal interconnect [a wide portion of the metal layer 74 in the layer 58'], which is formed on the via plug, formed in said multilayered film, wherein

the dielectric constant [k] of said etching stopper is larger than that of said first and second dielectric films (k=1.4-3.5 for the first and second dielectric films, k=1.1-5.5 for etching stopper; col. 4, lines 9-64).

Fig. 8 of Gates shows most aspects of the instant invention except "the upper surface of said etching stopper is located under the upper surface level of said metal interconnect, the under

surface of said etching stopper is located over the under surface level of said metal interconnect, and the under surface of said metal interconnect is located inside the first dielectric film," and "the etching stopper is positioned substantially below the middle level in the height of said metal interconnect." Figure 10 of Watanabe shows a metal interconnect [30] wherein the upper surface of the etching stopper [24] is located under the upper surface level of said metal interconnect, the under surface of said etching stopper is located over the under surface level of said metal interconnect, and the under surface of said metal interconnect is located inside the first dielectric film [23] and the etching stopper is positioned substantially below the middle level in the height of said metal interconnect.

It would have been obvious to one of ordinary skill in the art at the time of the invention was made to incorporate the teachings of Watanabe into the device of Gates in order to have the upper surface of the etching stopper located under the upper surface level of said metal interconnect, the under surface of the etching stopper located over the under surface level of the metal interconnect, and the under surface of the metal interconnect located inside the first dielectric film while the etching stopper is positioned substantially below the middle level in the height of said metal interconnect to reduce a problem caused by residual masking material.

Regarding claims 2 and 19, Gates discloses the semiconductor device wherein the dielectric constant [k=1.1-5.5] of said etching stopper is less than or equal to 5 (col. 4, lines 60-64).

Regarding claims 3, 4, 20 and 21, Gates discloses the semiconductor device wherein the

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dielectric constant of said etching stopper is larger than or equal to a summation of 2 and the dielectric constant of either one of the dielectric constants [k=1.4-3.5] of said first and second dielectric films (col. 4, lines 15-20).

Regarding claims 5 and 22, Gates discloses said metal interconnect includes copper as a constituting element (col. 7, lines 30-35).

Response to Arguments

Applicant's arguments with respect to pending claims have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Junghwa M. Im whose telephone number is (571) 272-1655. The examiner can normally be reached on MON.-FRI. 8:30AM-5:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Richard T. Elms can be reached on (571) 272-1869. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Junghwa M. Im

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